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More than Moore Analog Electronics for Harsh Environment Applications

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CentraleSupélec

Who we are?



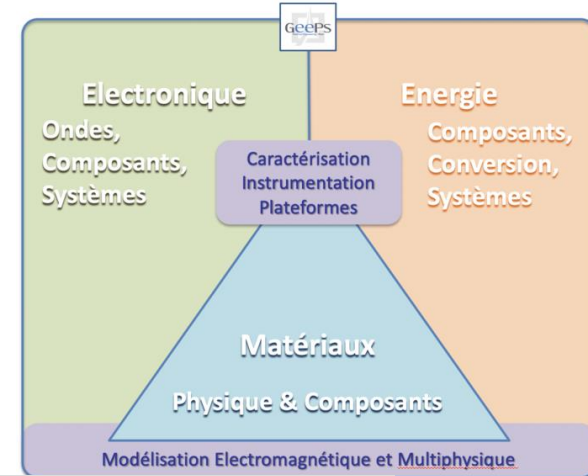
Plateau de Saclay



Université Paris-Saclay



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SHANGHAI RANKING

2021 Global Ranking of Academic Subjects

ShanghaiRanking began to publish world university ranking by academic subjects in 2009. By introducing improved methodology, the Global Ranking of Academic Subjects (GRAS) was first... [Read More](#)

2021

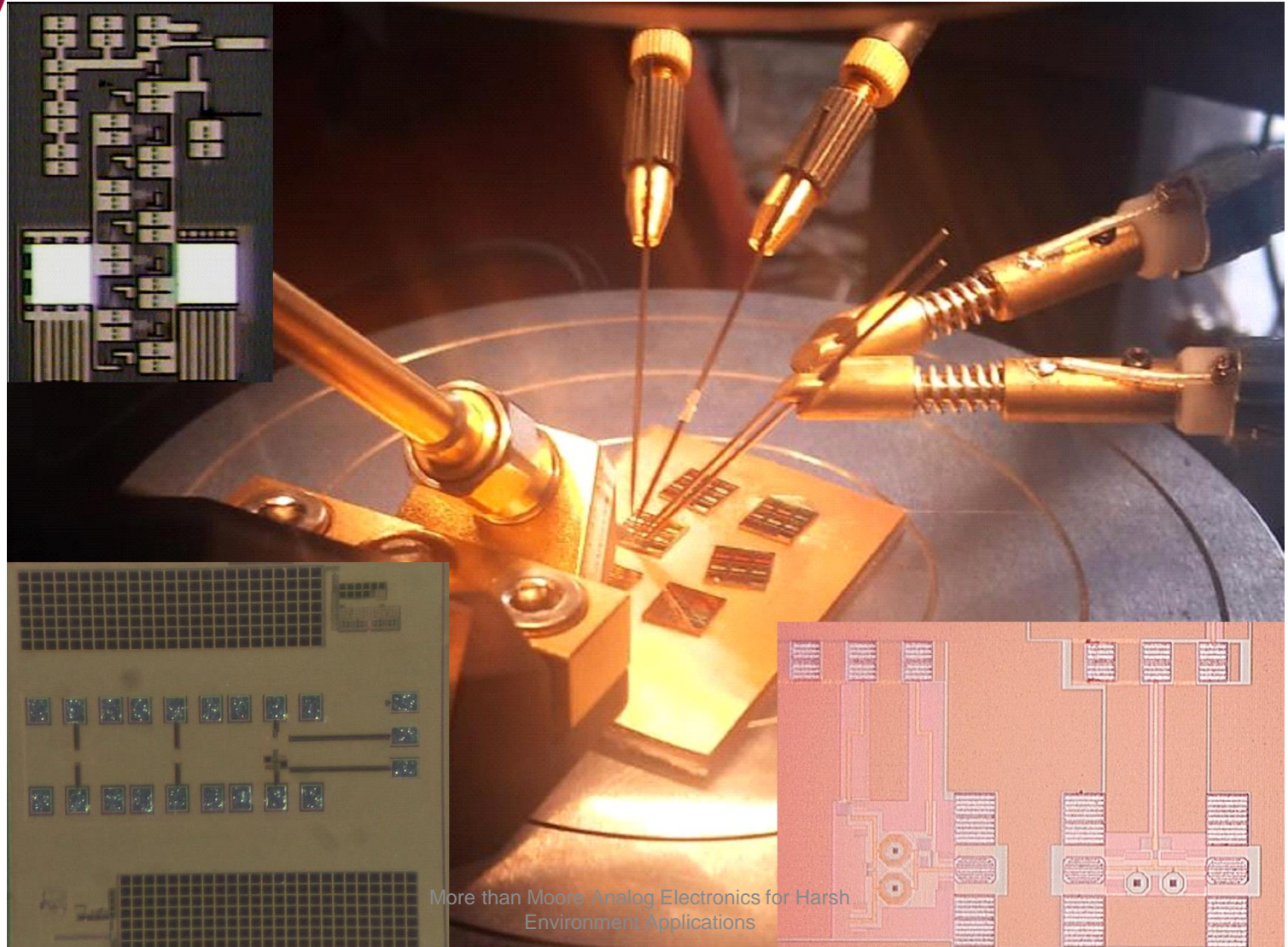
Electrical & Electronic Engineering

Search a University France

	Paris-Saclay University France	51-75
	Université Grenoble Alpes France	76-100
	Sorbonne University France	151-200



What we do research in Electronics?



More than Moore Analog Electronics for Harsh Environment Applications



Content

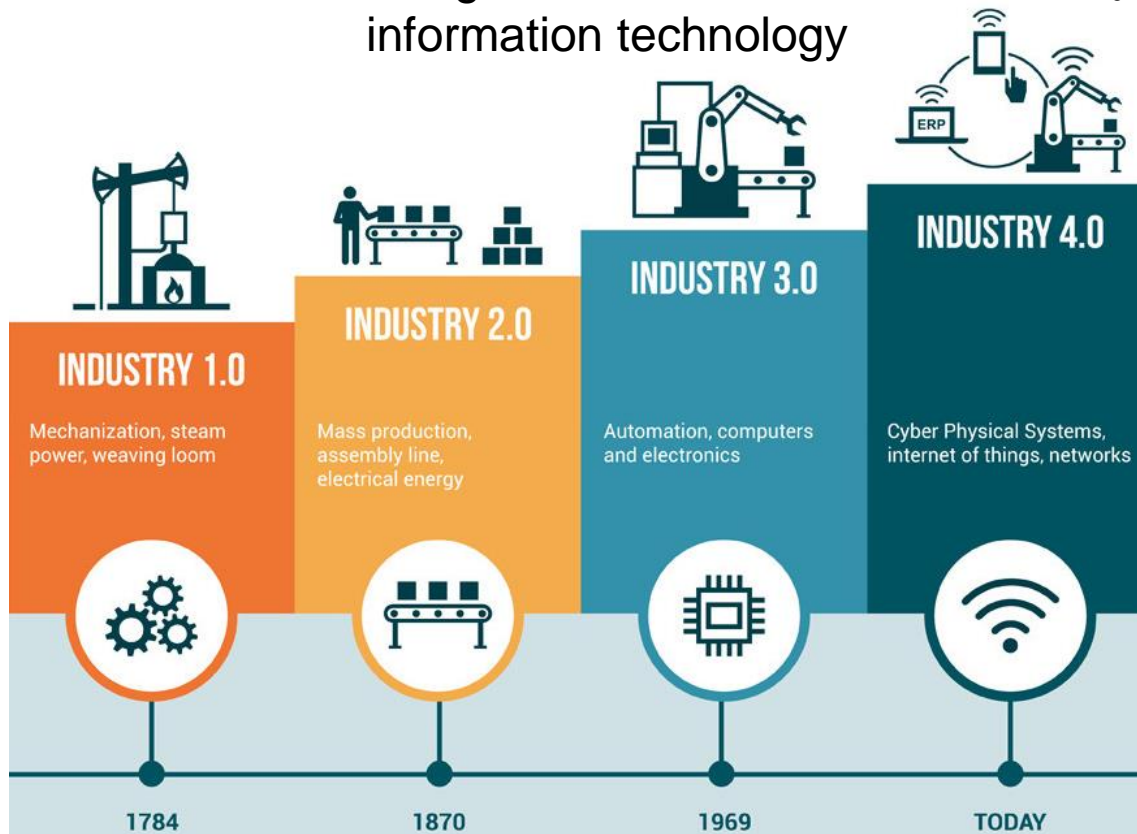
- Why do we need Research in Electronics ?
- How do we do Research in Electronics ?
- Research Trend Topics
 - More than Moore Analog Electronics
 - Electronics for Harsh Environments



Industrial Revolution

- Industry 3.0
 - Processes Automation using electronics and information technology

- Industry 4.0
 - Smart and Green Industry – a **1.3 billion dollars** worldwide investment



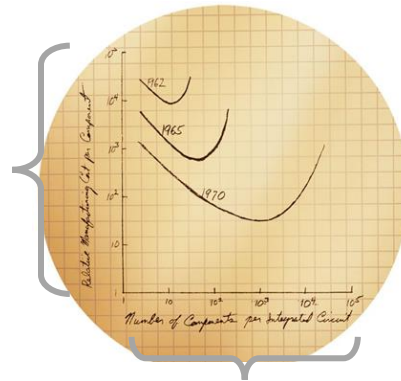
Moore's Law

1965: Moore's Law: Prediction of future of integrated circuits

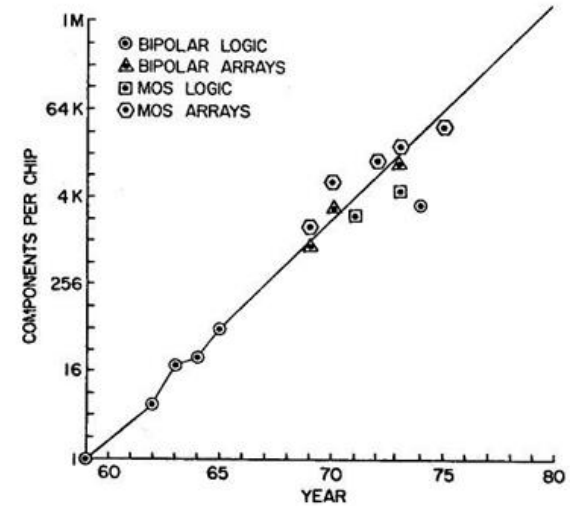
Integration density versus time

Integrated circuits market

\$/circuit



transistors/circuit



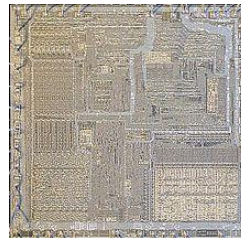
Theoretical limit: 8-12 nm

Source:

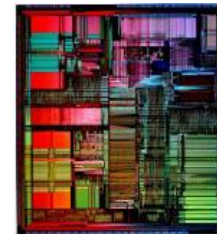
D. J. Frank, R. H. Dennard, E. Nowak, P. M. Solomon, Y. Taur, and H. S. P. Wong, "Device scaling limits of Si MOSFETs and their application dependencies," *Proc. IEEE*, vol. 89, no. 3, pp. 259–287, 2001.

<http://www.computerhistory.org/>

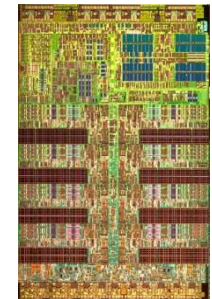
<http://www.tayloredge.com/museum/processor/processorhist.ory.html>



20 k transistors
Intel 8086 – **1978**
3 μm



3.1 M transistors
Intel Pentium - **1993**
0.35 μm

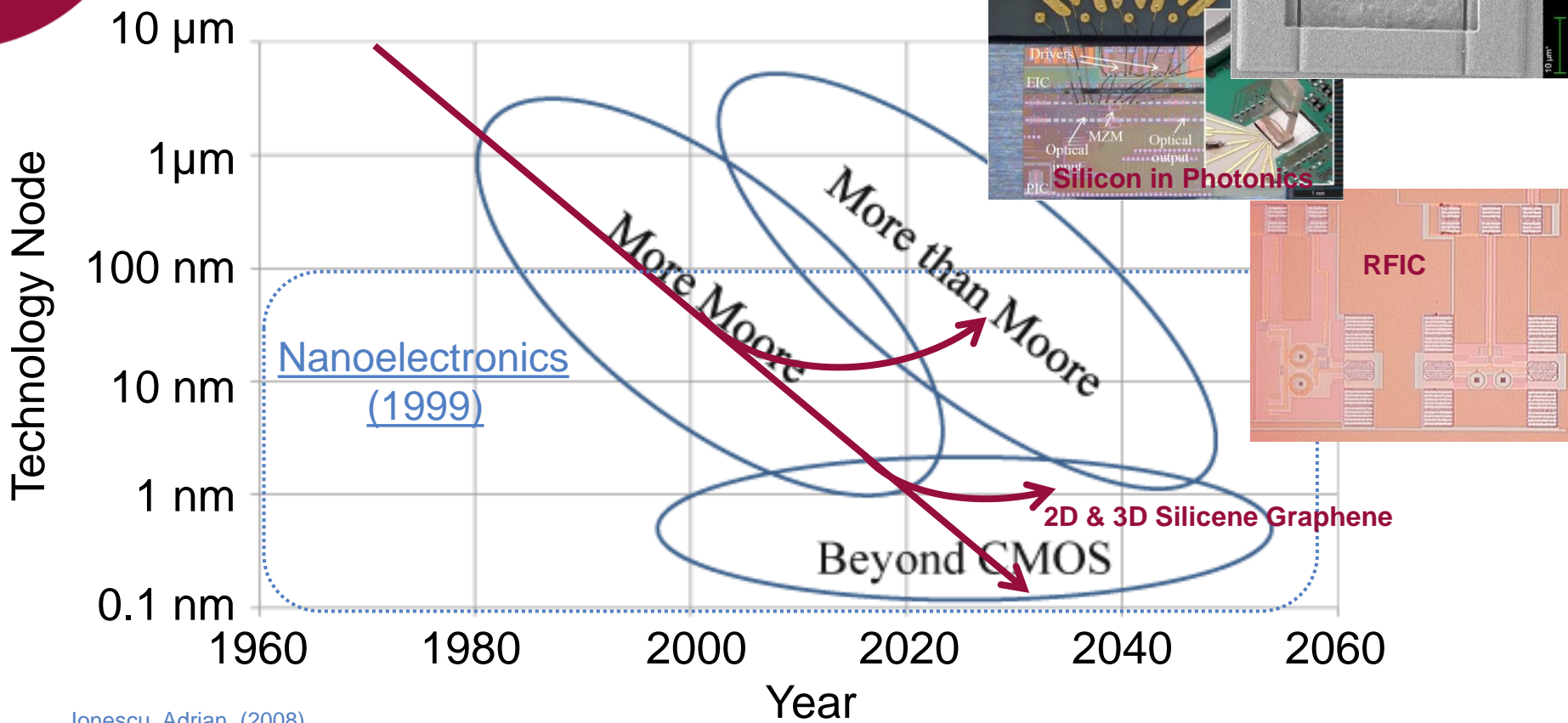


1.6 B transistors
PlayStation 3 - **2006**
90 nm

More than Moore Analog Electronics for Harsh Environment Applications



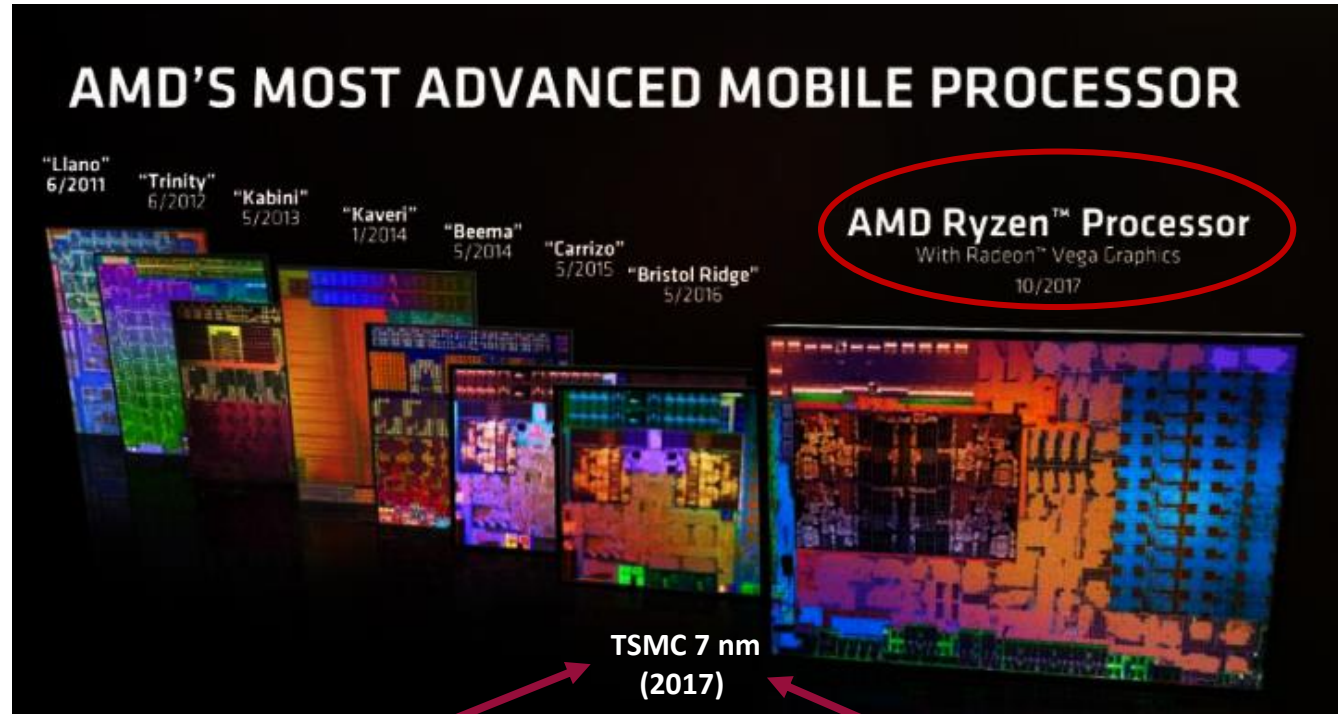
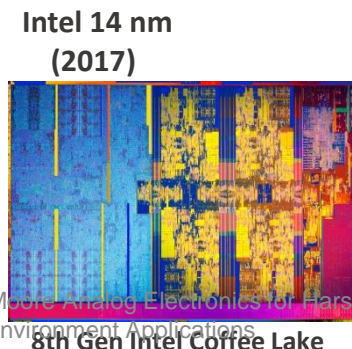
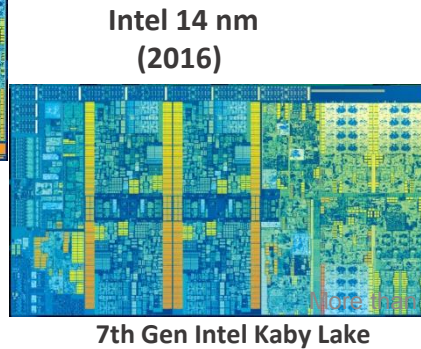
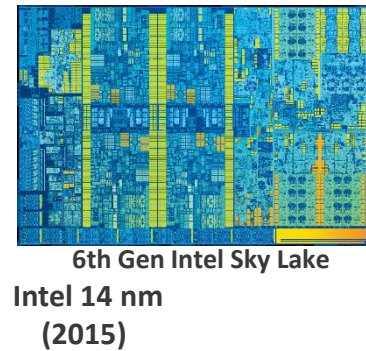
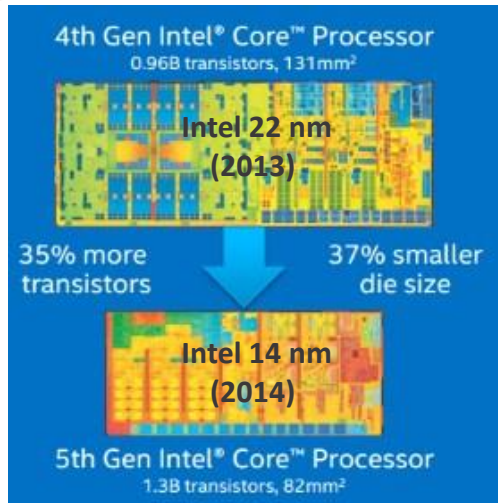
More Moore and Beyond



Ionescu, Adrian. (2008).
Nanoelectronics roadmap: evading
Moore's law.



Electronics Economy



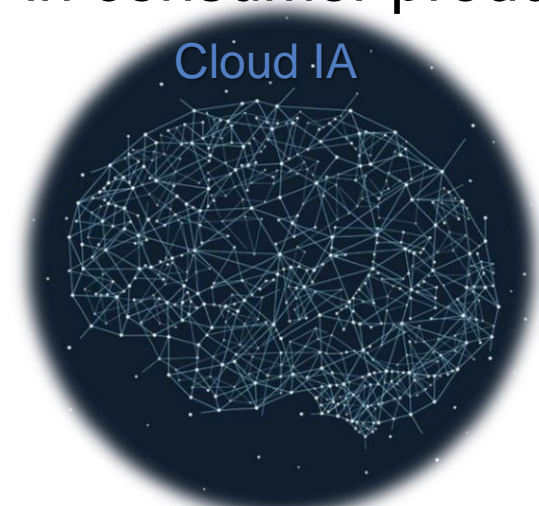


Industrial Revolution 4.0

- Internet-of-Things (IoT) are introducing new power and decision autonomous electronics in consumer products



- Needs:
 - Ultra-low power
 - AI-edge
 - Real time



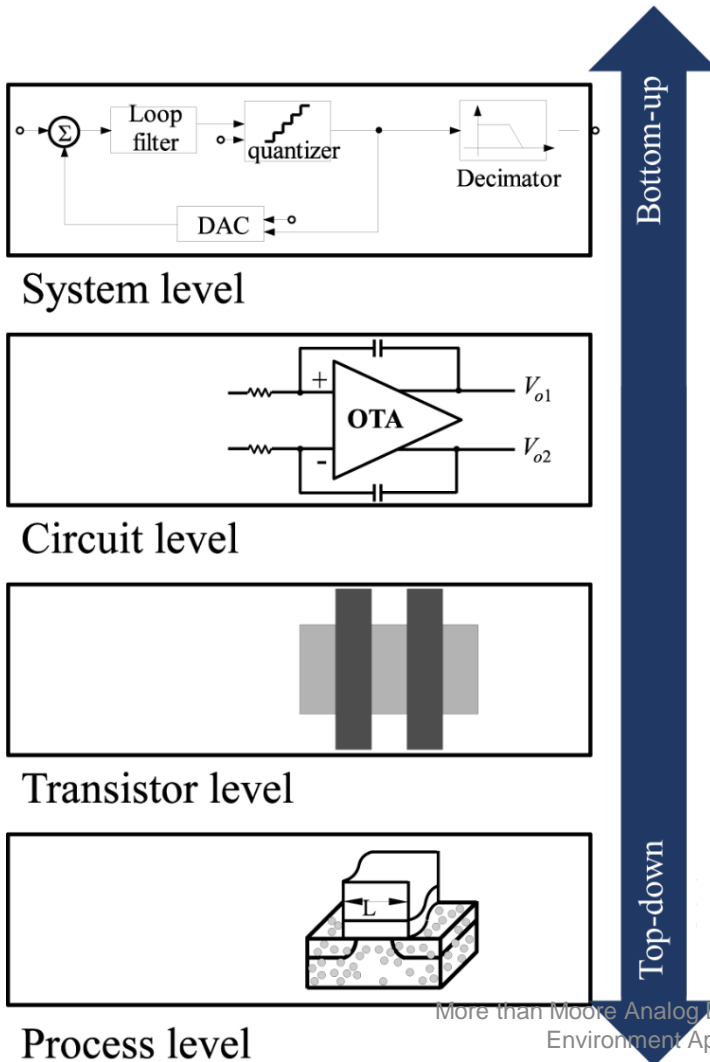


Content

- Why do we need Research in Electronics ?
- How do we do Research in Electronics ?
- Research Trend Topics
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Electronics – Hierarchical Discipline



$$A_v \geq 2^{bits}$$

$$P_{tot} \leq 100 \text{ mW}$$

$$P_{DC} = I_D \cdot V_{DD}$$

$$A_v = g_m \cdot R_L$$

$$g_m/I_D \quad f_T$$

$$g_m/g_{DS} \quad f_{CO}$$

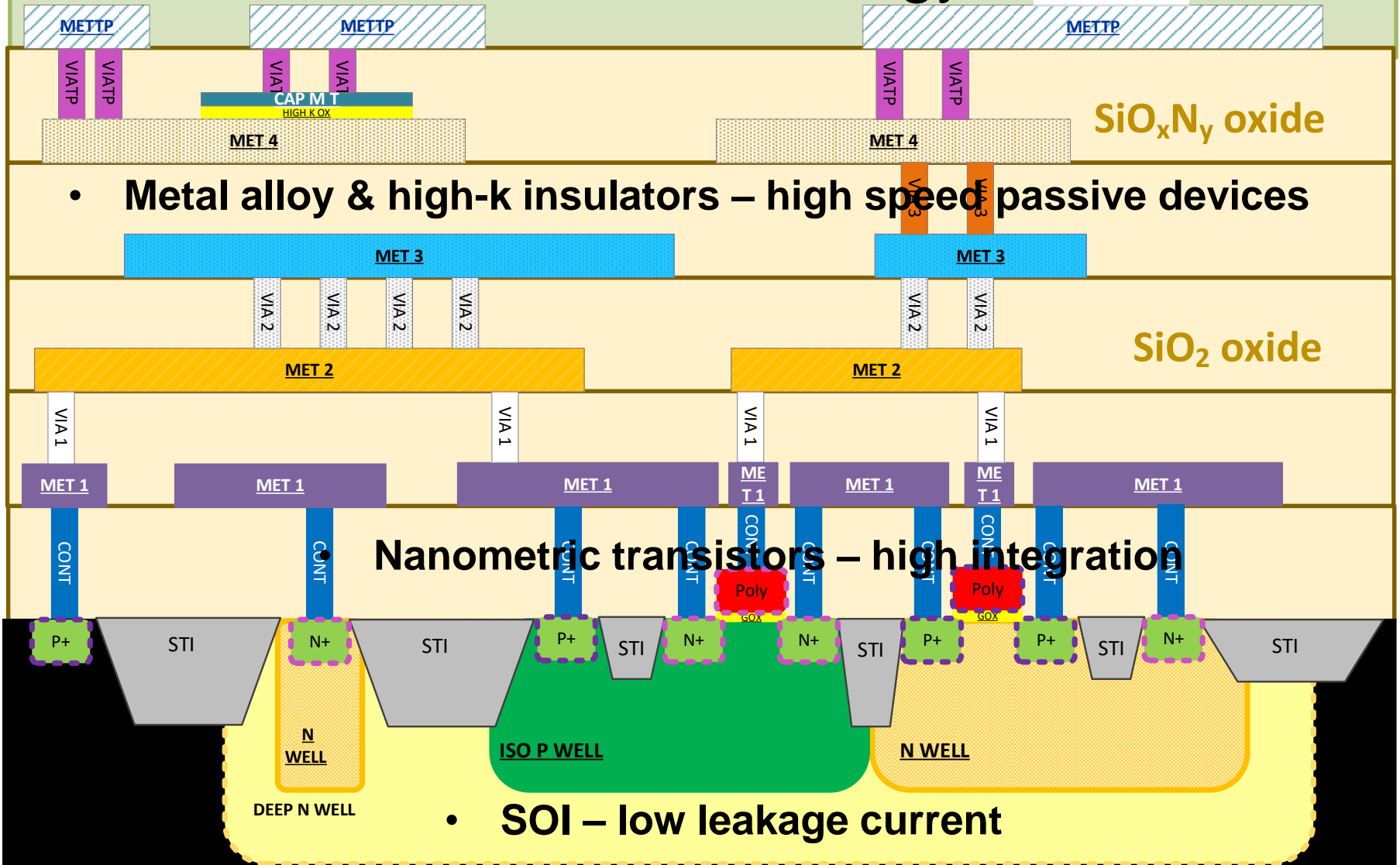
BSIM6, PSP, UICM

$$I_D = \eta g_m \phi_t \left[1 + \frac{g_m}{2\mu_n C_{ox} \phi_t (W/L)} \right]$$

SiN Passivation Layer

PAD

Process Level – SOI Technology



SiO_xN_y oxide

SiO₂ oxide

- Metal alloy & high-k insulators – high speed passive devices

Nanometric transistors – high integration

- SOI – low leakage current

- Modelling – BSIM6, PSP, UICM



Transistor Level – from Weak to Strong inversion MOSFET

Weak inversion (WI)

$$I_{WI} = I_S e^{V_{GS}/\eta\phi_t} \longrightarrow I_{WI} = \eta g_m \phi_t$$

Strong inversion (SI)

$$I_{SI} = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{th})^2 \longrightarrow I_{SI} = \frac{\eta g_m^2}{2 \mu_n C_{ox} (W/L)}$$

V_{th} is the threshold voltage at $V_{SB} = 0$, W/L is the geometric ratio, μ_n is the mobility, n is the slope factor (from 1.1 to 1.5), and C_{ox} is the oxide capacitance per unit area



Transistor Level – All-region “interpolation” model

$$I_{WI} = \eta g_m \phi_t \quad \xrightarrow{\text{interpolation}} \quad I_{SI} = \frac{n g_m^2}{2 \mu_n C_{ox} (W/L)}$$

For $g_m \rightarrow \infty$, I_{WI} is negligible;

while for $g_m \rightarrow 0$, I_{SI} is negligible

$$I_D = I_{WI} + I_{SI} = \eta g_m \phi_t \left[1 + \frac{g_m}{2 \mu_n C_{ox} \phi_t (W/L)} \right]$$


$$I_D = I_{WI} \left[1 + \frac{(W/L)_{th}}{(W/L)} \right] \Leftrightarrow g_m = 2 \mu_n C_{ox} \phi_t (W/L)_{th}$$

where $(W/L)_{th}$ is the normalized aspect ratio



Transistor Level – The Unified Current Control Model (UICM)

$$g_{ms} = \frac{\partial I_D}{\partial V_S}, g_m = \frac{\partial I_D}{\partial V_G} \therefore g_m = \frac{g_{ms}}{\eta}$$



$$g_{ms} = \frac{\partial I_D}{\partial V_S} = -I_S \frac{\partial if}{\partial V_S} = \frac{2I_S}{\phi_t} (-1 + \sqrt{1 + if})$$

$$-\frac{V_T}{2} \frac{\partial if}{(-1 + \sqrt{1 + if})} = \partial V_S$$

$$V_P - V_S = \phi_t [\sqrt{1 + if} - 2 + \ln(-1 + \sqrt{1 + if})]$$

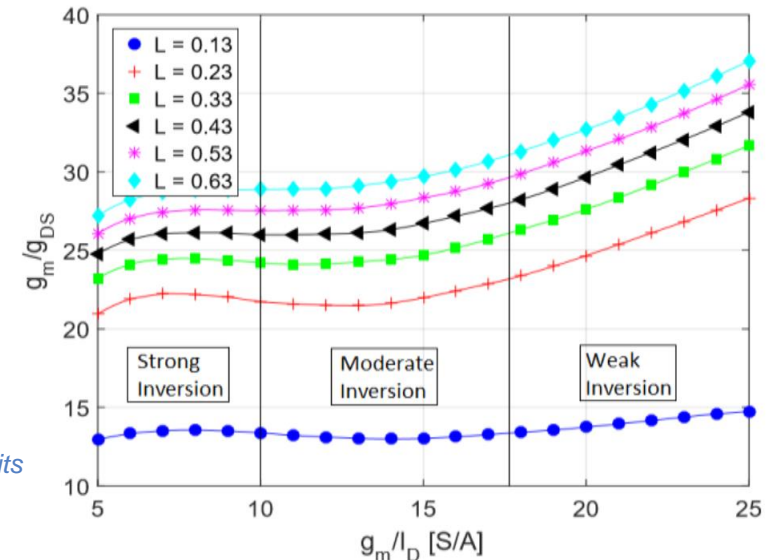
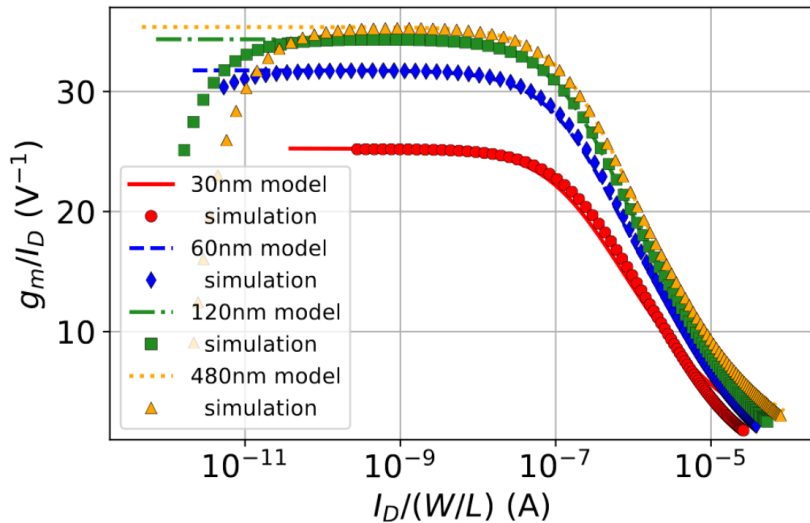
$$V_P = \frac{V_G - V_{th}}{\eta}$$

V_P (pinch-off voltage) comes from the channel length modulation effect

C. Galup, M. Schneider, and I. Si, "The compact all-region MOSFET model: theory and applications," in *IEEE New Circuits Syst. Conf.*, 2018, pp. 166–169.

Circuit Level – g_m/I_D Methodology

- Black box approach
- Design of Experiments
- Intuitive Design

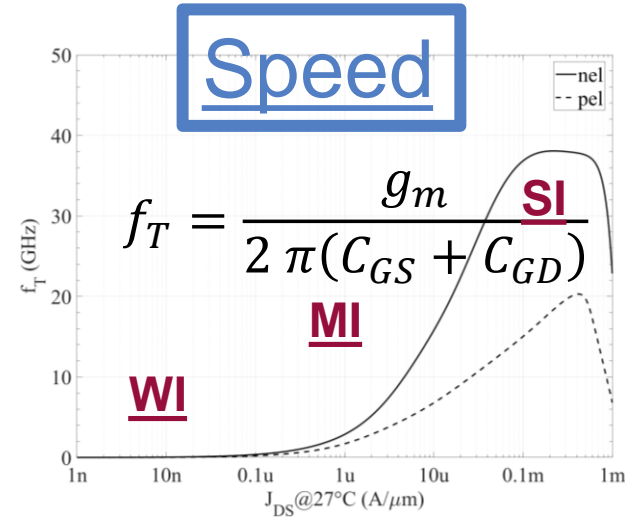
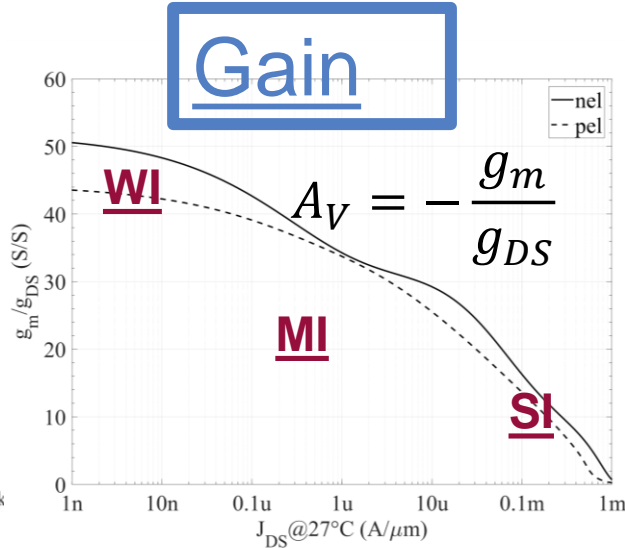
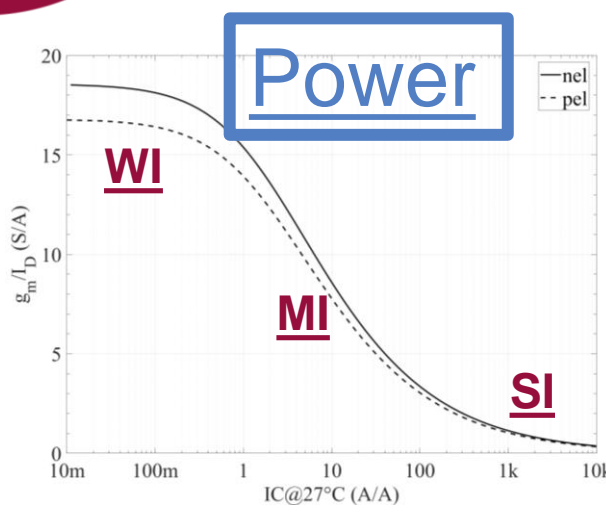


P. G. A. Jespers and B. Murmann, *Systematic Design of Analog CMOS Circuits Using Pre-Computed Lookup Tables*. Cambridge University Press, 2017.

$$\frac{\eta g_m \phi_t}{I_D} = \frac{2}{1 + \sqrt{1 + if}} \longrightarrow \frac{g_m}{I_D} = \frac{2}{\eta \phi_t (1 + \sqrt{1 + if})}$$

Circuit Level – Find the best Trade-off

- EDA Optimization problems



Area

$$P = V_{DD} \cdot \sum I_D$$

$$J_{DS} = \frac{I_D}{W}$$

Noise

$$f_{CO} = \frac{K_f}{C_{ox}L} \cdot \frac{g_m}{I_D} \cdot \frac{J_{DS}}{4kT\gamma}$$

$$\frac{GBW}{SR} = \frac{g_m}{I_D}$$

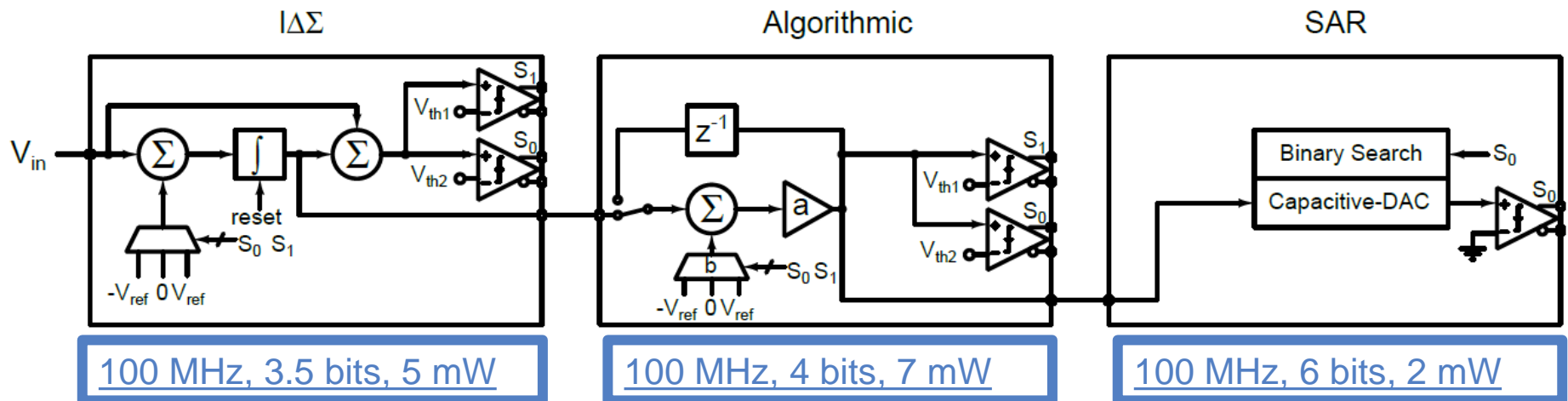
$$S = L \cdot \sum W_i$$

J. Ou and P. M. Ferreira, "Implications of Small Geometry Effects on gm/ID Based Design Methodology for Analog Circuits," *IEEE Trans. Circuits Syst. II, Exp. Briefs*, vol. 66, no. 1, pp. 81–85, Jan. 2019.

J. Ou and P. M. Ferreira, "A gm/ID-Based Noise Optimization for CMOS Folded-Cascode," *IEEE Trans. Circuits Syst. II, Exp. Briefs*, vol. 61, no. 10, pp. 783–787, Oct. 2014.

System Level – Hybrid ADCs

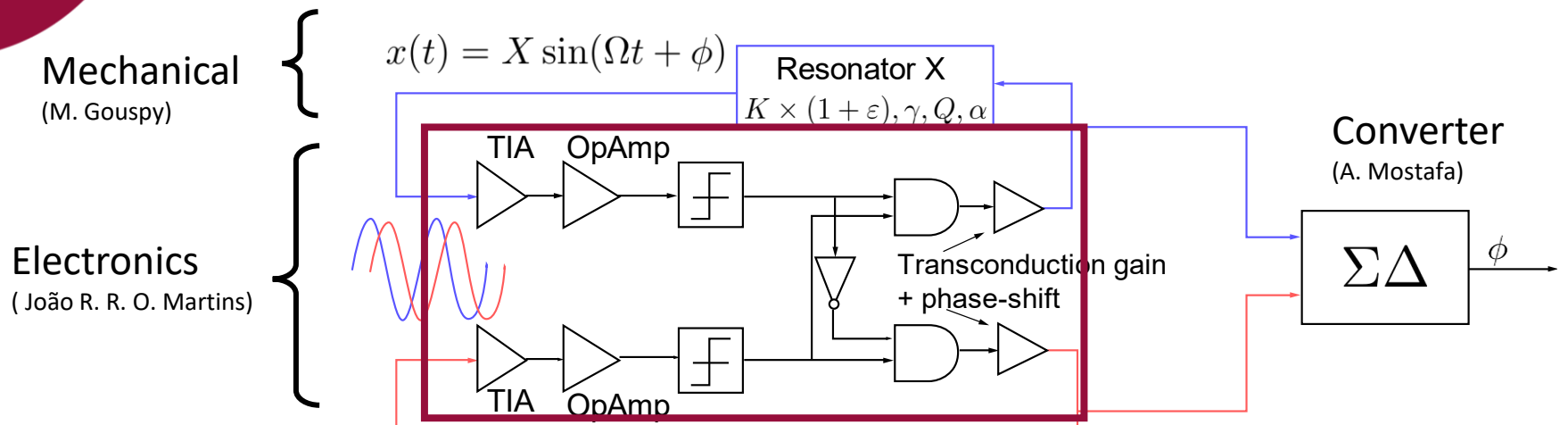
- Novel Topologies as hybrid and heterogeneous solutions
- Performance constraint share
 - Faster, higher resolution and low power



Ph.D. L. Cron ADC proposal

A. V. Fonseca, et al. "A Temperature-Aware Analysis of SAR ADCs for Smart Vehicle Applications," *J. Integr. Circuits Syst.*, vol. 13, no. 1, pp. 1–10, Aug. 2018.

System Level – MEMS instrumentation



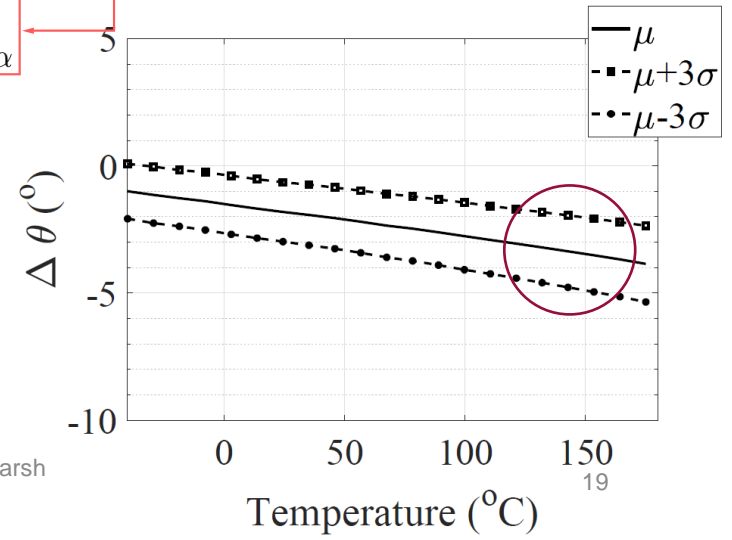
$$x(t) = X \sin(\Omega t + \phi)$$

$$y(t) = Y \sin(\Omega t + \phi)$$

$$\phi = \frac{\pi}{2} \cdot (1 + 2Q\epsilon)$$

$$\phi = \frac{\pi}{2} \cdot \left(1 + 2Q \left(\epsilon + \frac{\sqrt{2}}{2Q} \cdot \Delta\theta \right) \right)$$

Unreliable
Electronics



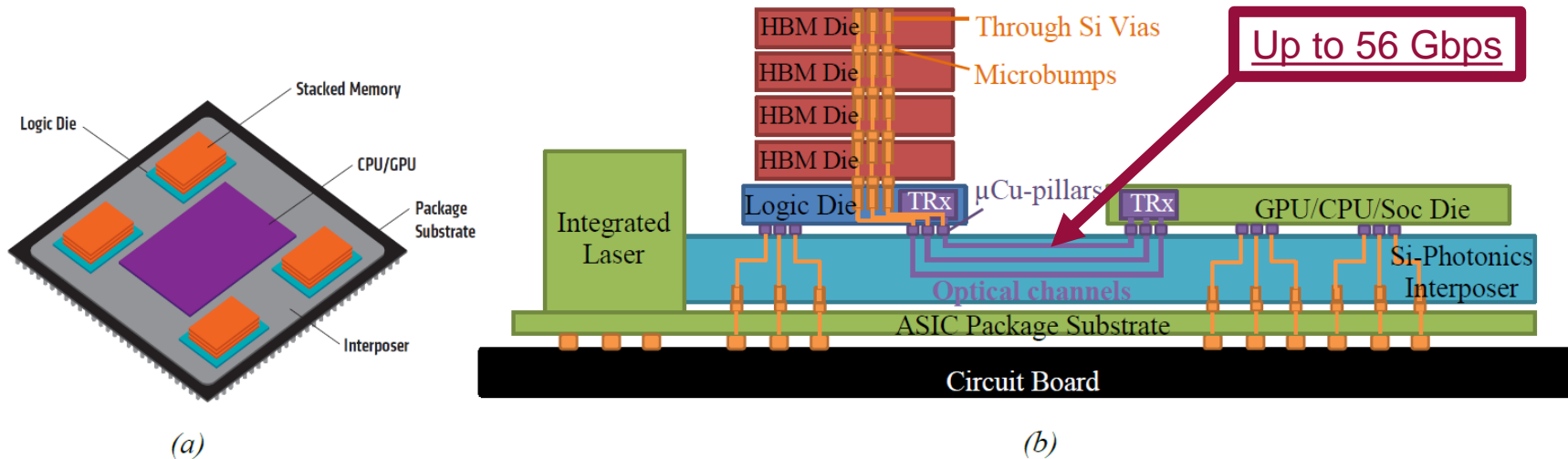


Content

- Why do we need Research in Electronics ?
- How do we do Research in Electronics ?
- **Research Trend Topics**
 - More than Moore Analog Electronics
 - Electronics for Harsh Environments



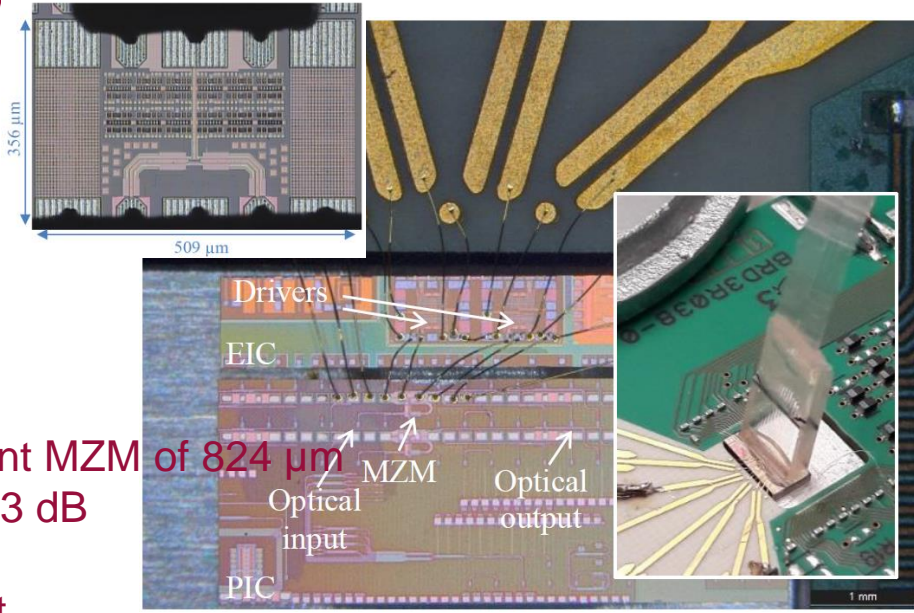
More than Moore: Silicon in Photonics



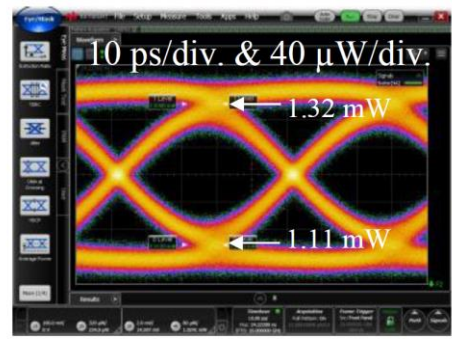
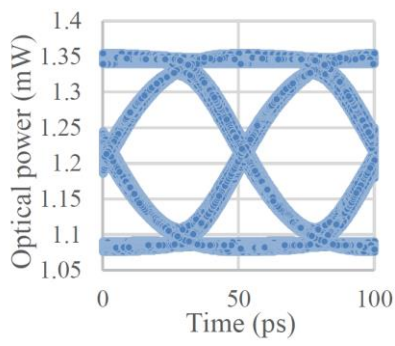
- Better data transmission – Light is not bounded to wire connection limitations (8 Gbps for PCIe)
- Higher integration costs – Requires a SiP post processing
- Smaller footprint – Computer Motherboard in a single ASIC

A 0.9 pJ/bit, low-ER SiP transmitter

Ph.D. A. Michard solution

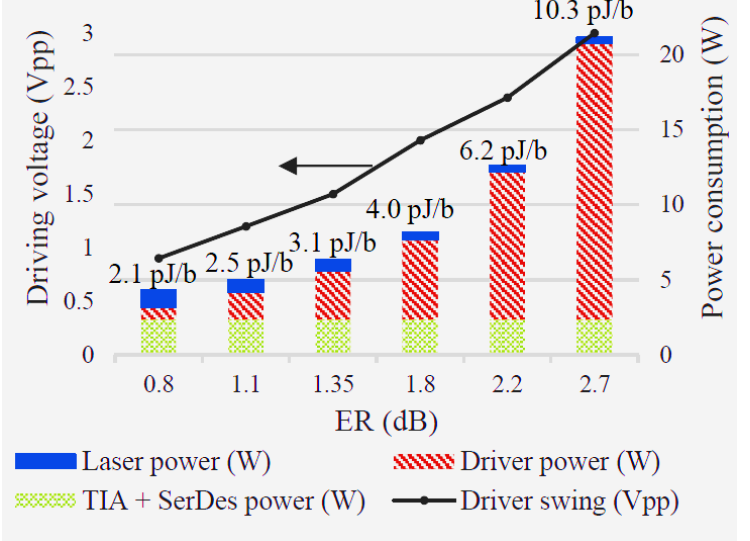


1 segment MZM of 824 μm
 ER = 0.73 dB
 20 Gbps
 0.9 pJ/bit



- Heterogenous SiP solution – bond wires connection
- System-level Optimization
 - Power consumption
 - Extinction Ratio reduction
 - 20 Gbps data rate

A. Michard, et al., "A sub-pJ/bit, low-ER Mach-Zehnder-based Transmitter for chip-to-chip Optical Interconnects," *J. Sel. Top. Quantum Electron.*, vol. 26, no. 2, p. 8301910, 2020.

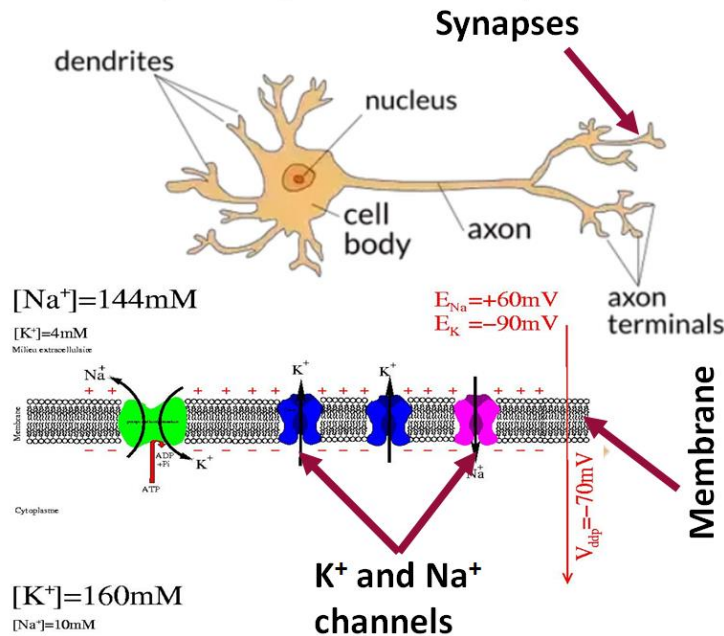


More than Moore: Artificial Intelligence

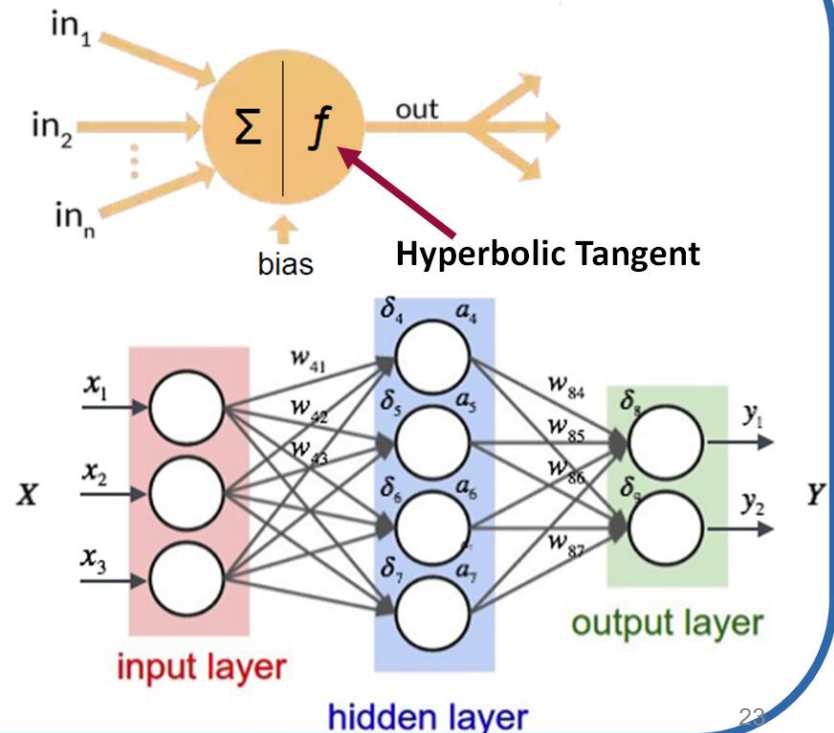
- Biological Solutions
 - Ion charge conduction
 - Living cells

- Software Solutions
 - Binary based
 - Von Neumann Computer

Biological neuron



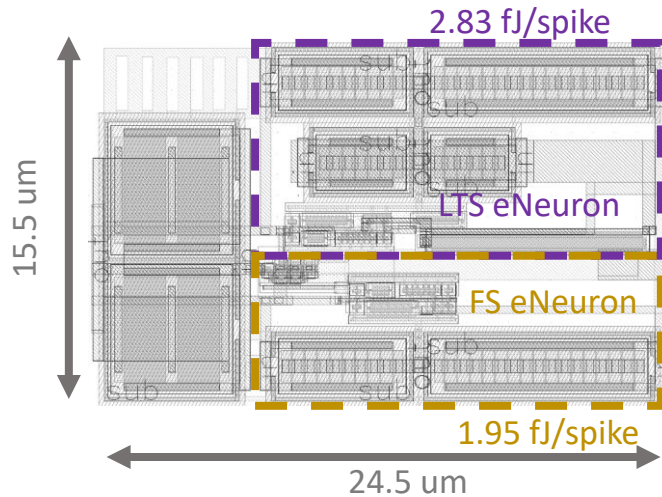
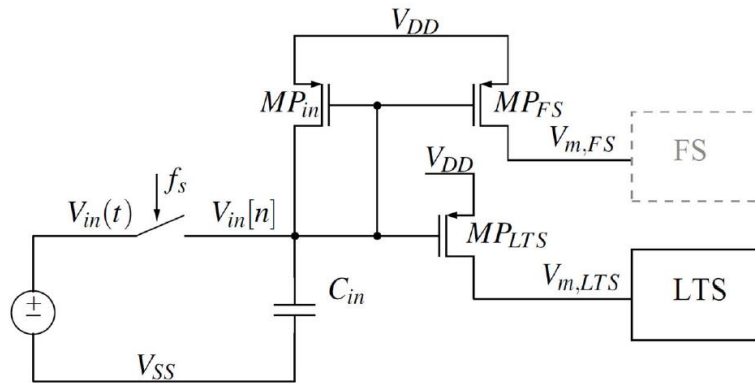
Artificial neuron





Neuromorphic Analog Spiking-Modulator

a 55 nm Integrated SNN solution



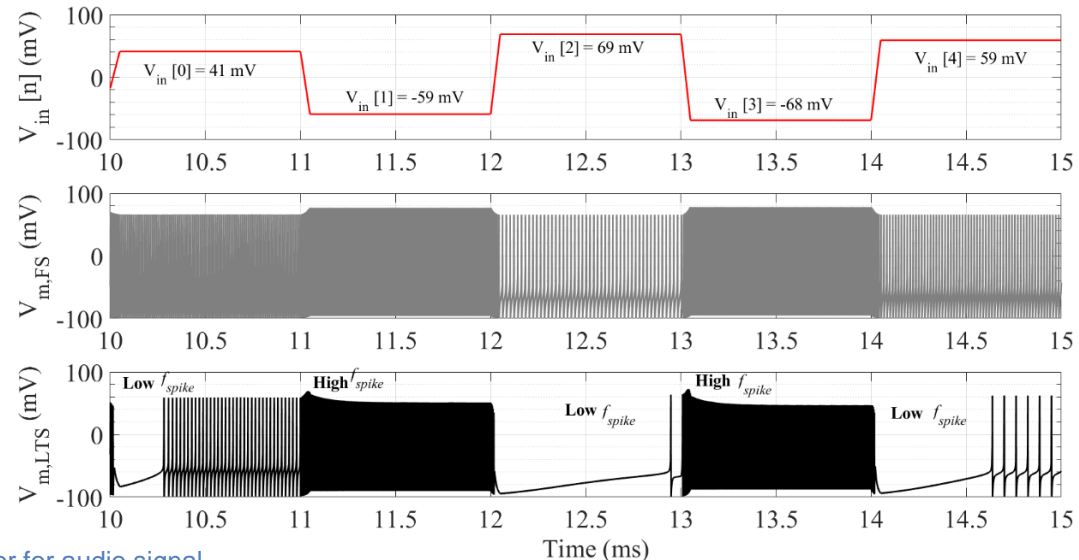
- Analog Hardware Solutions

- Neuron model validated

I. Sourikopoulos *et al.*, "A 4-fJ/spike artificial neuron in 65 nm CMOS technology," *Front. Neurosci.*, vol. 11, no. 123, pp. 1–14, Mar. 2017.

- Lack of plasticity in synapses

G. Indiveri *et al.*, "Neuromorphic silicon neuron circuits," *Front. Neurosci.*, vol. 5, no.5, pp. 1–23, May 2011.



Ferreira, P.M., *et al.* Neuromorphic analog spiking-modulator for audio signal processing. *Analog Integr Circ Sig Process* **106**, 261–276 (2021).
<https://doi.org/10.1007/s10470-020-01729-3>

More than Moore Analog Electronics for Harsh Environment Applications

NASP: 9 bits de resolution, 8 fJ/conv

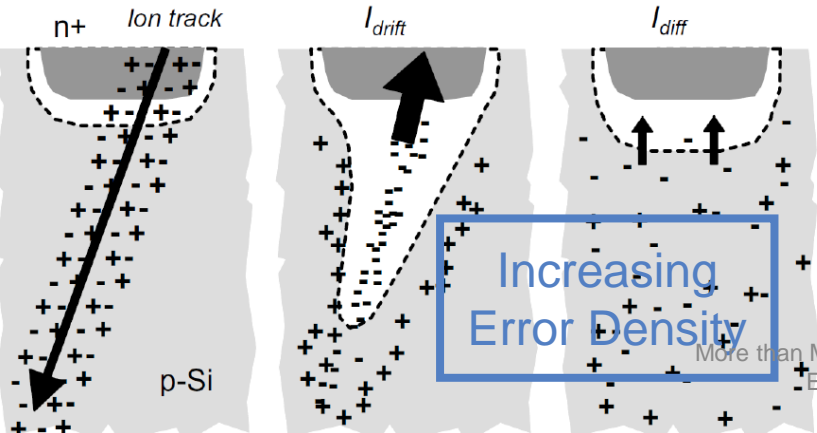
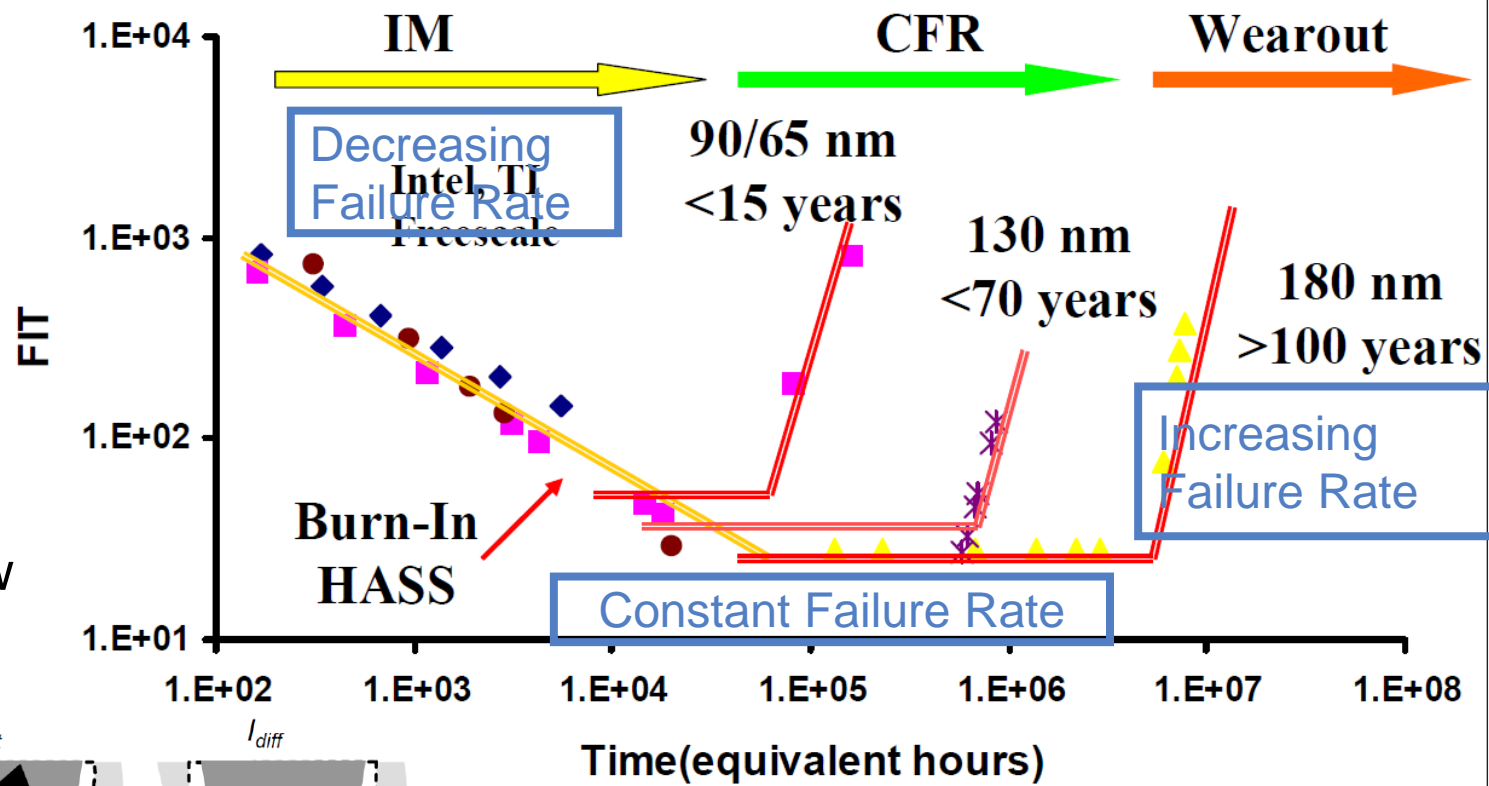


Content

- Why do we need Research in Electronics ?
- How do we do Research in Electronics ?
- **Trend Research**
 - More than Moore Analog Electronics
 - **Electronics for Harsh Environments**

Harsh Environments: Radiation and Aging

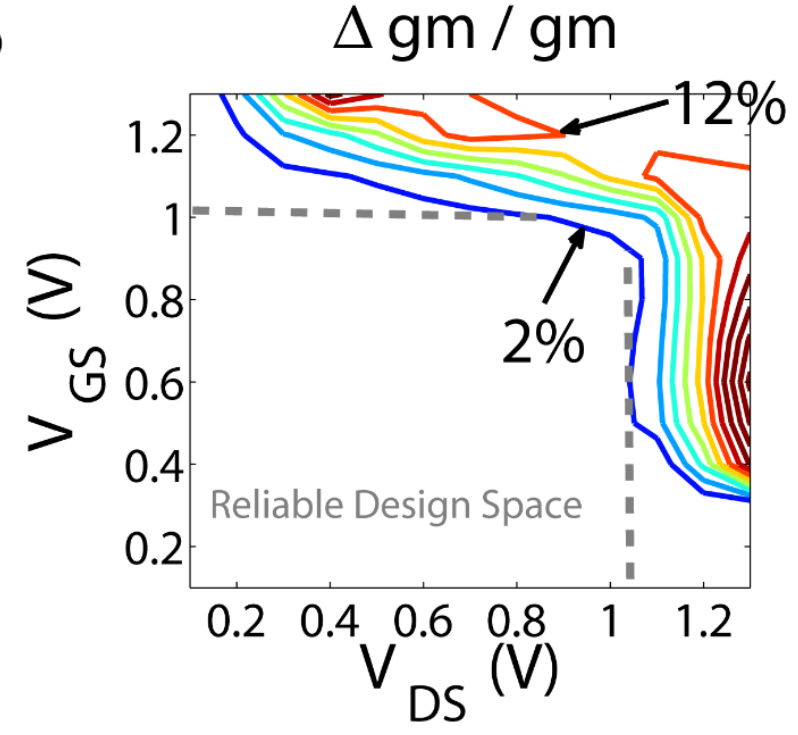
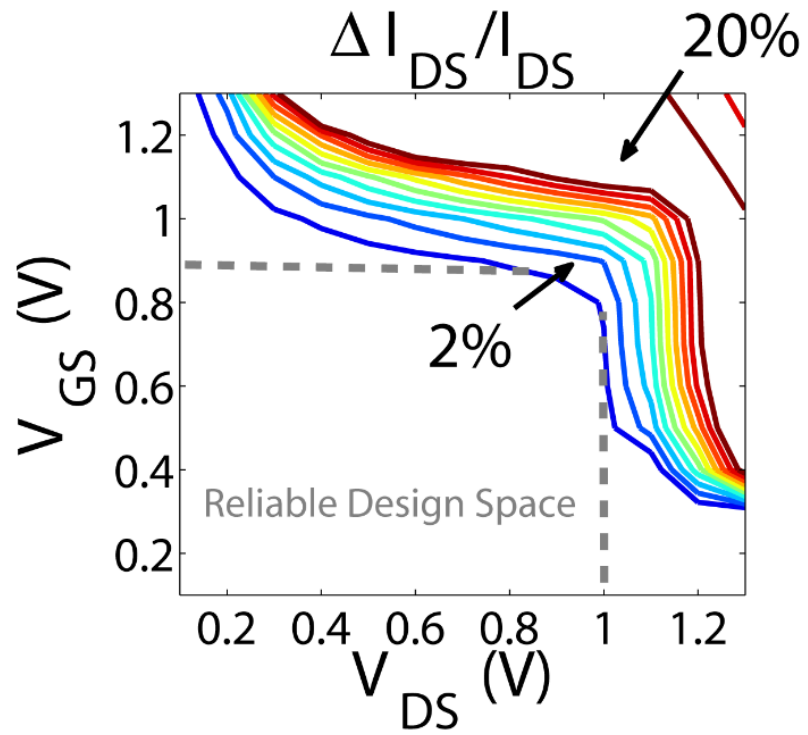
- Failure is increasing in nanometric electronics
- Transistor lifetime below few years!



M. White and Y. Chen, "Scaled CMOS Technology Reliability Users Guide," JPL Publication 08-14 3/08, 2008. (NASA report)



Transistor-level: Reliability Resilience

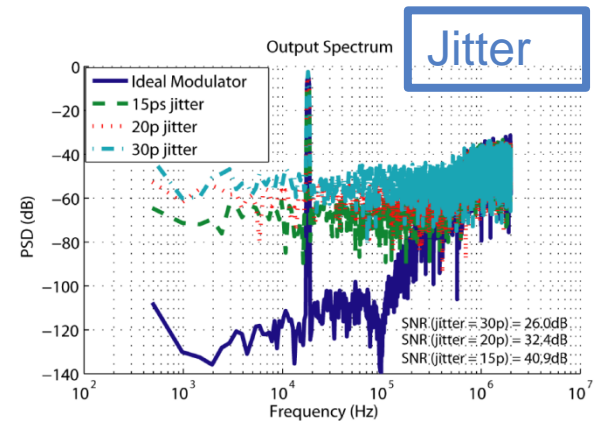
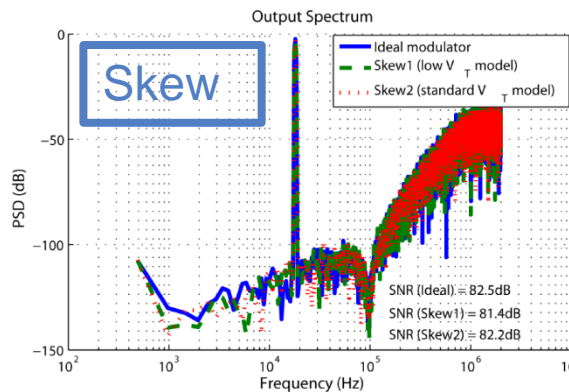
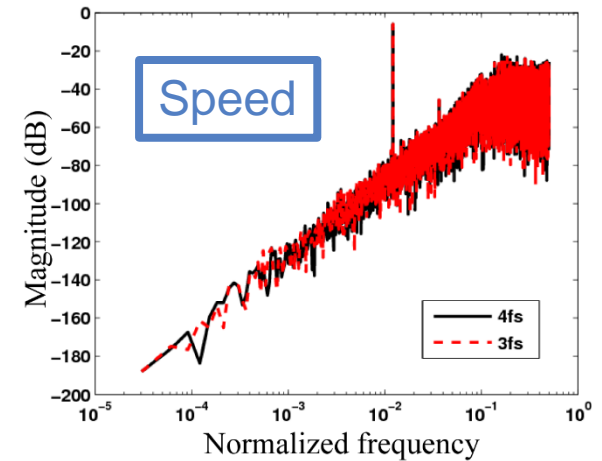
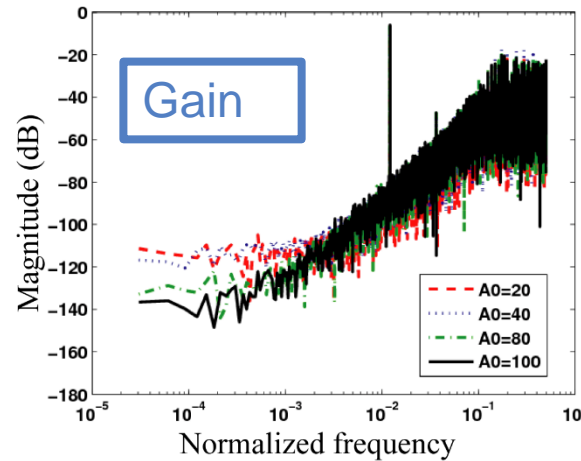


- Modeling HCI and NBTI of ST 65 nm
- Enable a g_m/I_D methodology
- Negligible aging – reliable design space

P. M. Ferreira, H. Petit, and J.-F. Naviner, "A New Synthesis Methodology for Reliable RF front-end Design," in *Proc. IEEE Int. Symp. Circuits Syst.*, 2011, pp. 1–4.
 P. M. Ferreira, H. Petit, and J.-F. Naviner, "A synthesis methodology for AMS/RF circuit reliability: Application to a DCO design," *Microelectron. Rel.*, vol. 51, no. 4, pp. 765–772, Dec. 2010.

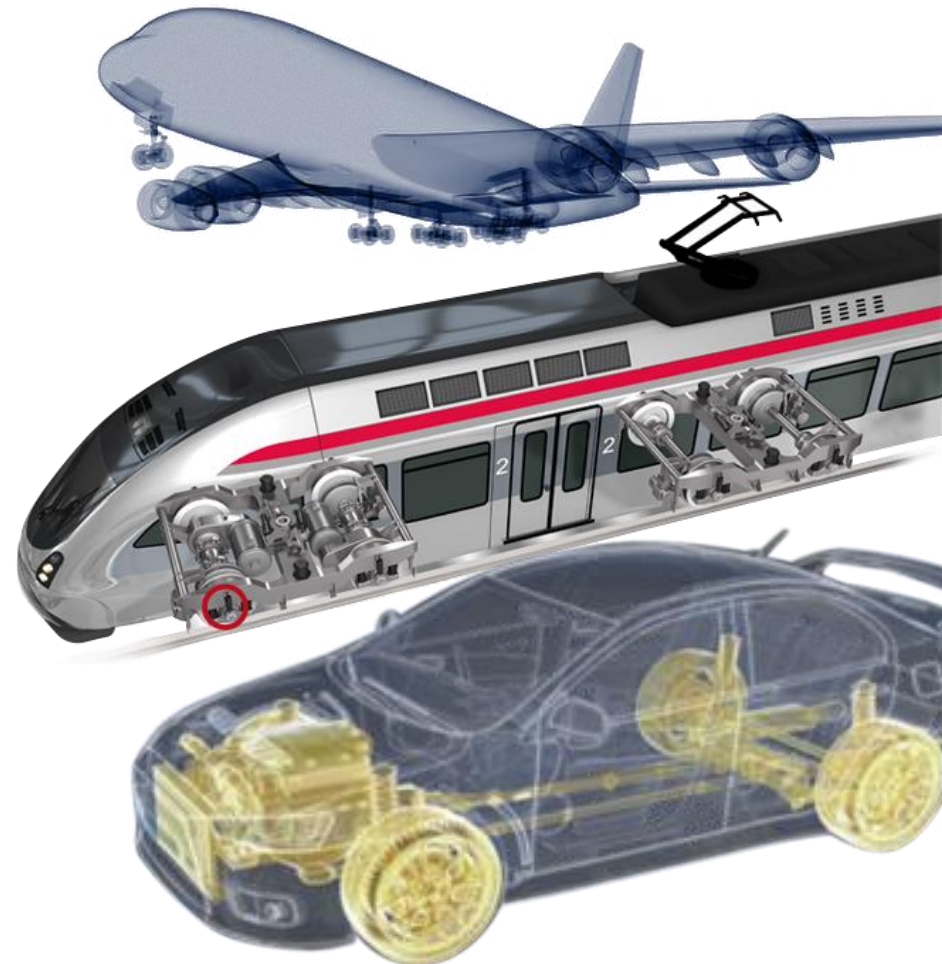
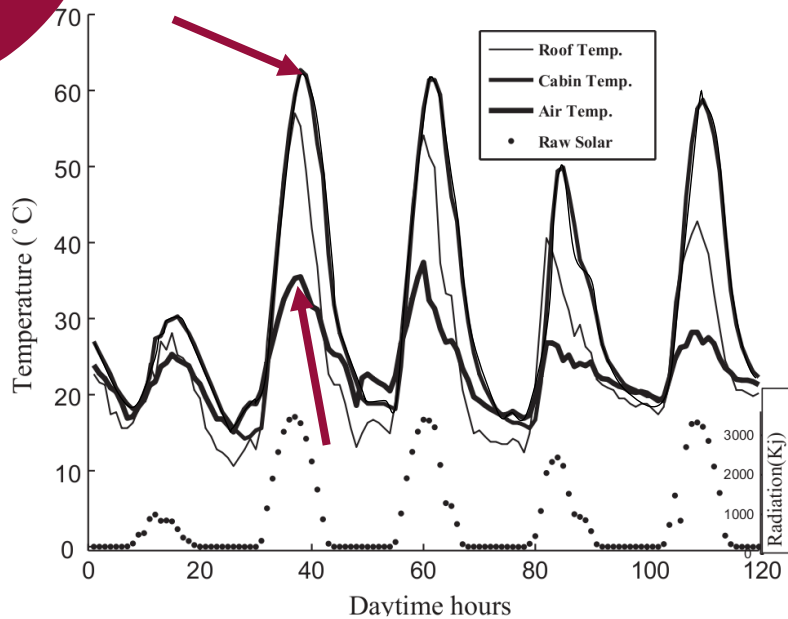
System-Level: Faulty building blocks

- Continuous Time $\Sigma\Delta$ ADC
- Building block failure tests
- OpAmp Failure
 - Gain drop
 - GBW limitation
- Clock
 - Skew
 - Jitter



P. M. Ferreira, H. Cai, and L. Naviner, "Reliability Aware AMS / RF Performance Optimization," in *Performance Optimization Techniques in Analog, Mixed-Signal, and Radio-Frequency Circuit Design*, Eds. IGI-Global, 2014, pp. 28–54.

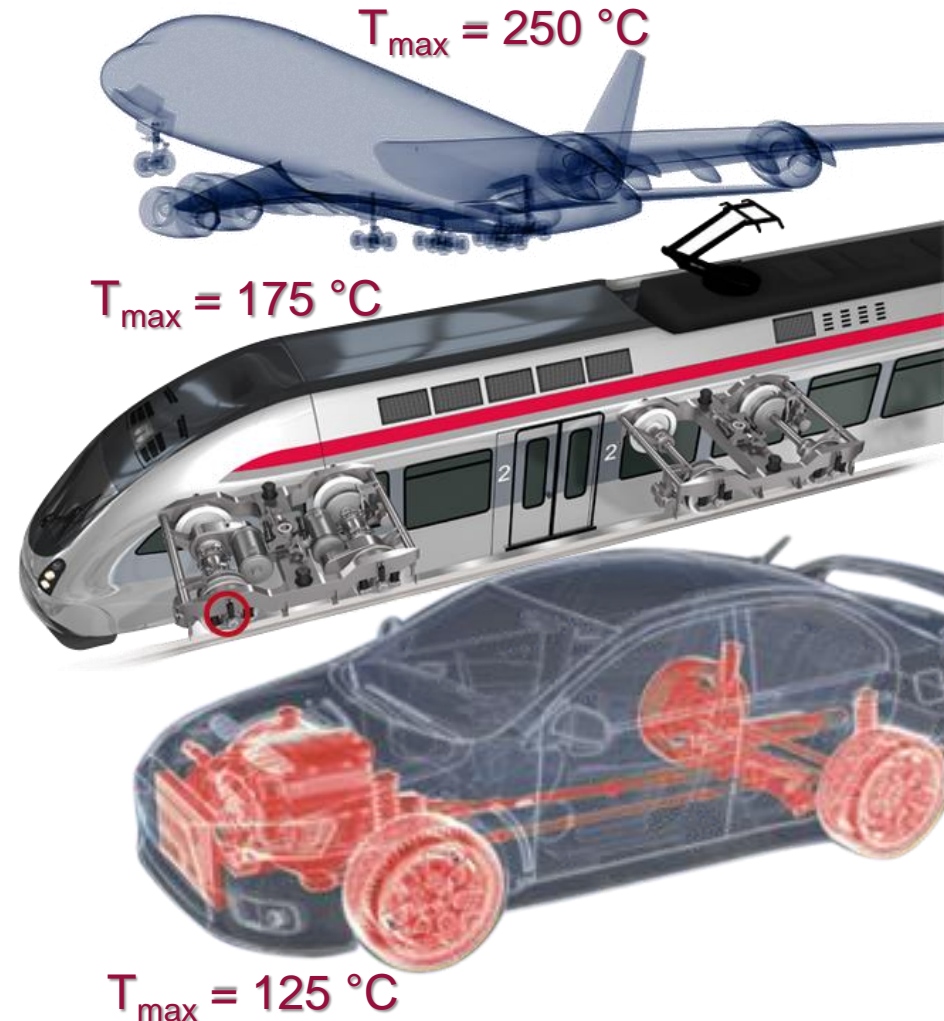
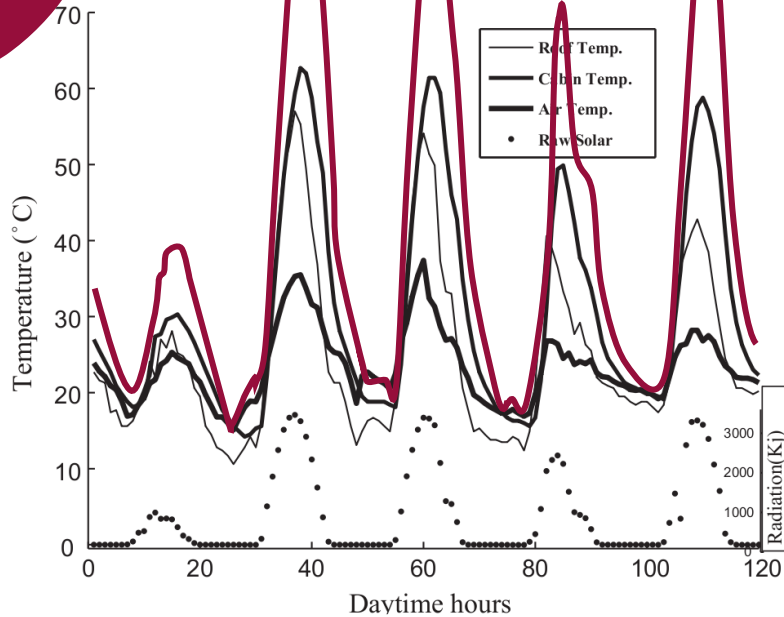
Harsh Environments: High Temperature



- Smart Vehicles – efficiently sense and communicate with other nearby devices
- Safety in working environment – high temperature
- Low costs – use standard processes, digital-enabled

More than 200 sensors expected

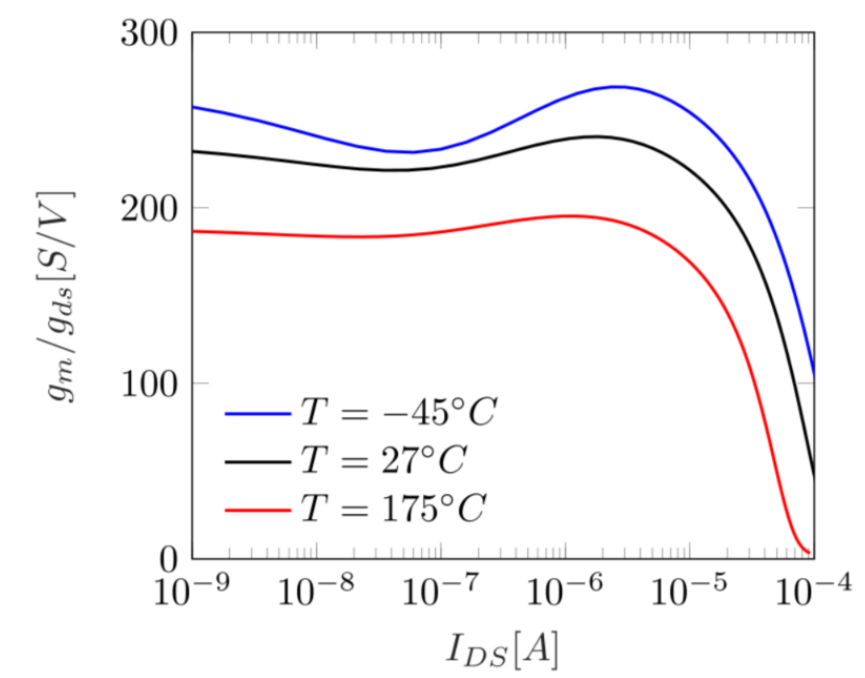
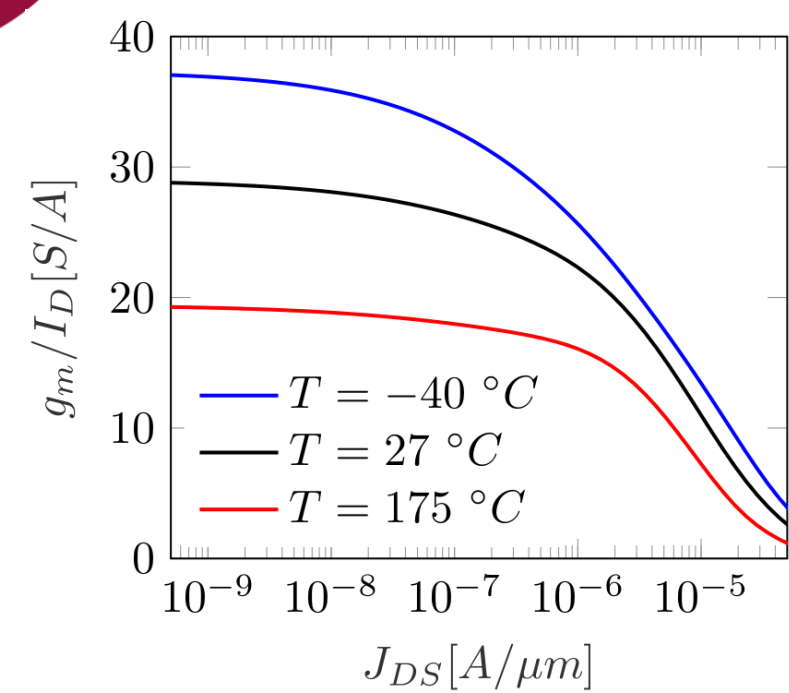
Harsh Environments: High Temperature



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g_m/I_D Methodology fails in high temperature

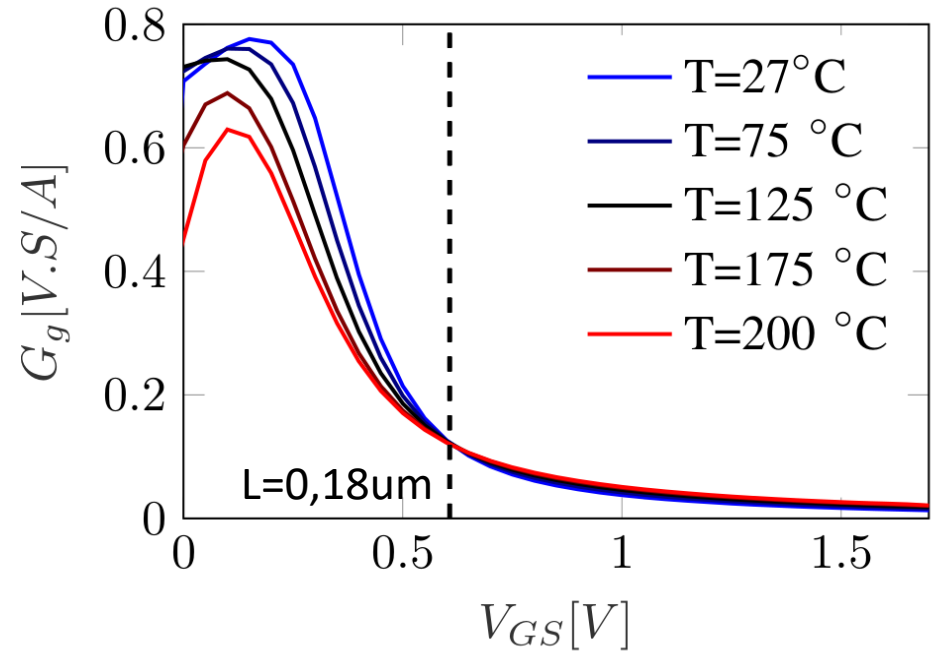
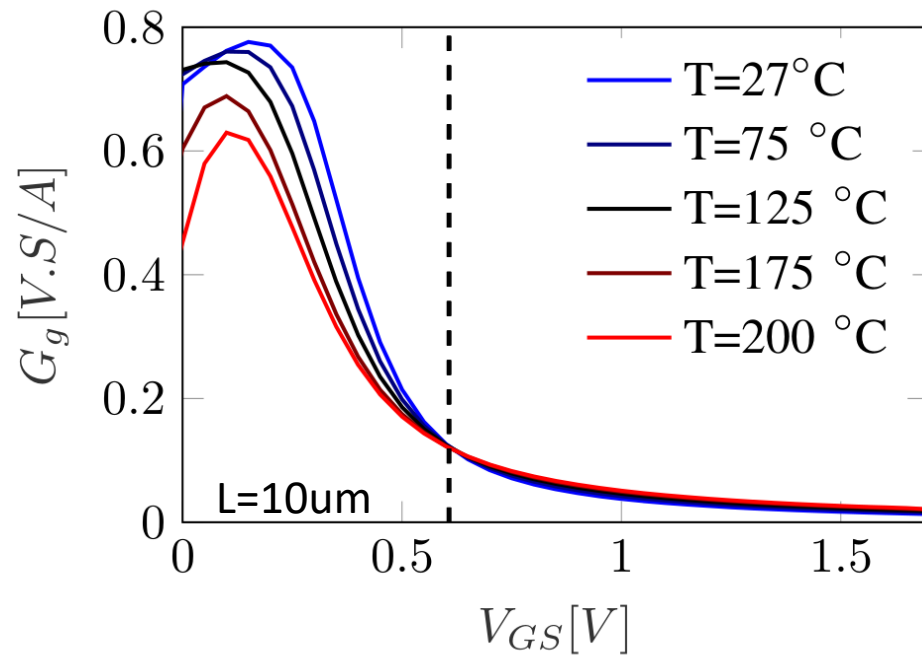


$$\frac{g_m}{I_D} = \frac{1}{\phi_t} \frac{2}{\eta(V_G)(q_{is}(V_G, V_S) + q_{id}(V_G, V_S) + 2)}$$

Temperature Dependency

Temperature Aware g_m/I_D Methodology

J. R. R. O. Martins, Ph.D. cand methodology



$$\frac{g_m}{I_D} = \frac{1}{\phi_t} G_g$$

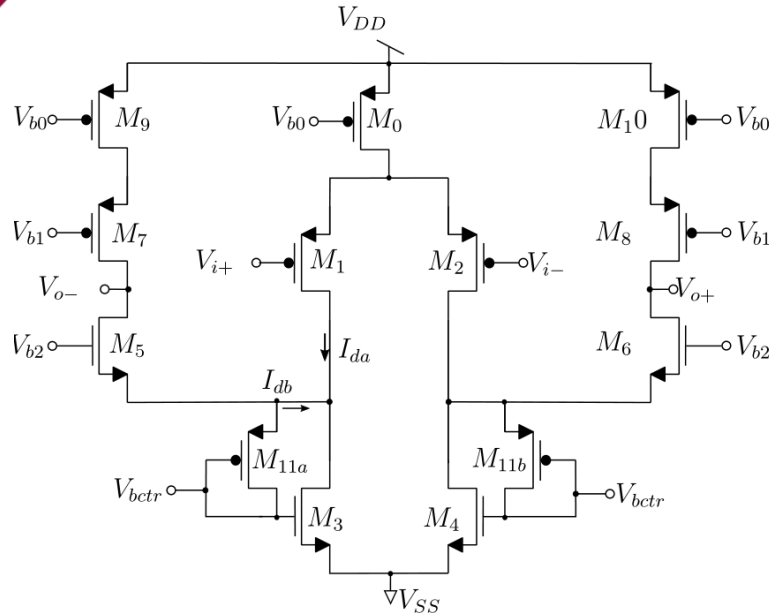
Temperature Normalized Parameter

J. R. R. De Oliveira Martins, et al., "A Temperature-Aware Framework on g_m/I_D -Based Methodology Using 180 nm SOI From -40°C to 200°C ," in IEEE Open Journal of Circuits and Systems, vol. 2, pp. 311-322, 2021, doi: 10.1109/OJCAS.2021.3067377.

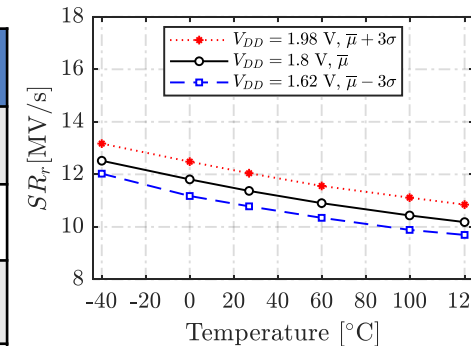
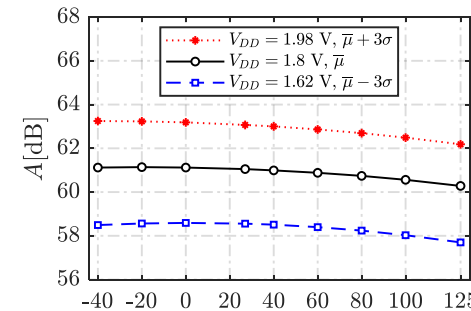
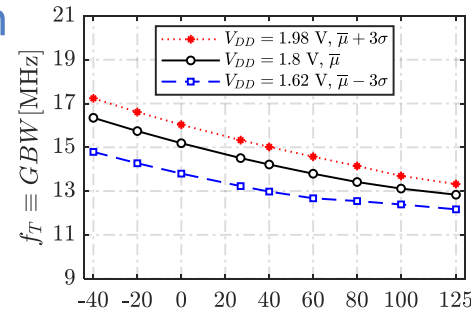


Temperature Aware OTA

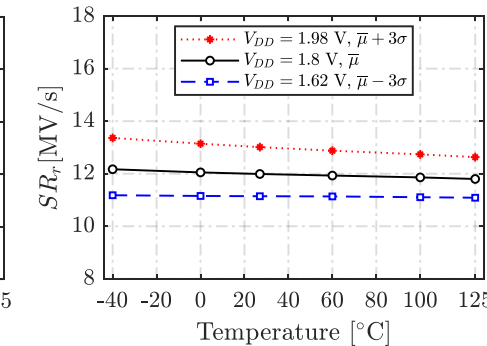
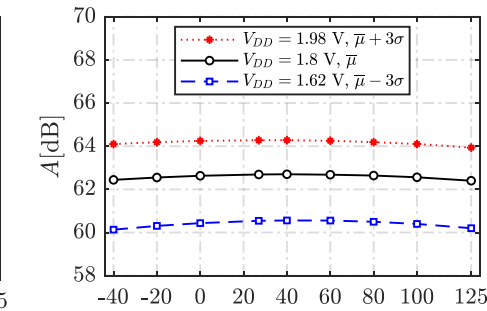
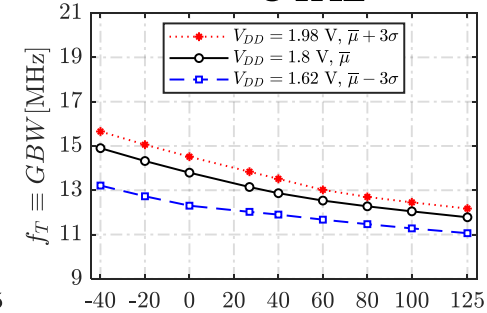
Ph.D. A. Mostafa design



OTA1



OTA2



Device	g_m/I_d	To minimize
M_0	6	$S_{I_{DS}}^T$
$M_{1(2)}$	9	$S_{g_m}^T$
$M_{3(4)}$ and $M_{5(6)}$	5 ($L = 3\mu m$)	$S_{I_{DS}}^T$ and $S_{g_{ds}}^T$
$M_{7(8)}$ and $M_{9(10)}$	6 ($L = 3\mu m$)	$S_{I_{DS}}^T$ and $S_{g_{ds}}^T$



Thank you very much

Questions?

